

ALD 2016 -16th International Conference on Atomic Layer Deposition

Veranstaltung - ALD 2016 -16th International Conference on Atomic Layer Deposition ↗

Titel	ALD 2016 -16th International Conference on Atomic Layer Deposition
Wann	So, 24. Juli 2016 - Mi, 27. Juli 2016

Beschreibung

ALD 2016 -16th International Conference on Atomic Layer Deposition

The 16th International Conference on Atomic Layer Deposition (ALD 2016) will be a three-day meeting dedicated to the science and technology of atomic layer controlled deposition of thin films. This year, the ALD conference will incorporate the Atomic Layer Etching 2016 Workshop, so that delegates at the two events can interact freely. The conference will take place on 24-27 July 2016 at the Convention Centre Dublin, Ireland.

Please find more information relating this event by following link:

<http://ald2016.com/>

Lokalität - Dublin

Standort	Dublin
Ortsname	Dublin
Land	IE